

GAS SUPPLY SYSTEM, PROCESSING APPARATUS, GAS SUPPLY METHOD, AND METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE

ABSTRACT

A technique includes a gas supply system including: a plurality of gas supply lines connected to a process chamber, wherein each of the plurality of gas supply lines includes an inlet-side valve through which a gas flows in, a storage in which the gas is accumulated through the inlet-side valve, and an outlet-side valve through which the gas flows out of the storage; and a regulator installed in at least one of the plurality of gas supply lines and is configured to be capable of regulating a flow path resistance of the gas supply line such that gas supply amounts from the plurality of gas supply lines into the process chamber are matched.

Fig. 4B